

Eximor[®] SV1 Filters

Advanced disposable POU filters for critical photo-solvent applications

Eximor[®] SV1 filters provide the ultimate particle retention with rapid flush-up in sub 30 nm technology wafer processing applications.

Using the most advanced membrane technologies, Eximor SV1 filters are specially designed for use on Tokyo Electron Limited (TEL[®]) tracks in various Reducing Resist Consumption (RRC) and Negative Tone Development (NTD) solvents. The specially designed ultra-high molecular weight polyethylene (UPE) based membrane thickness offers sieving and nonsieving retention technologies that remove various contaminants and tiny particulate. The result is the cleanest POU solution available with significantly lower on-wafer defects that ensures higher production yields.

Rapid Startup and Device Purity

Eximor SV1 filters use the unique Impact[®] 8G core-fill design for rapid priming that improves bubble clearance times. This priming time is further improved by an optimized and aggressive cleaning procedure designed specifically for solvents used in the targeted applications. This leads to even lower non-volatile residue (NVR) and metals extractables and ensures a flush-up time that is superior to other POU filters.

APPLICATIONS

- RRC solvents
- NTD developers



FEATURES & BENEFITS

Core fill structure

Reduces overall filter priming time leading to reduced filter startup costs

Efficient priming promotes a rapid, stable, repeatable environment with lower defectivity

Specially designed PE-based membrane technology

Reduces on-wafer defects in sub 30 nm technologies wafer processing

Ensures tight retention and low pressure drop performance

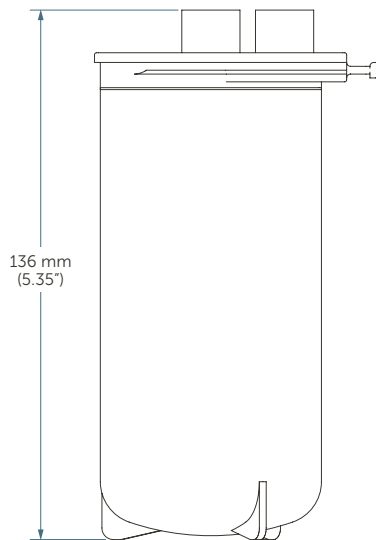
Additional nonsieving retention further reduces particles and ensures the cleanest on-wafer solvents possible at start-up

SPECIFICATIONS

Materials	Membrane	UPE
	Shell, core, supports	High-density polyethylene (HDPE)
	O-ring (OF)	Kalrez® perfluoroelastomer
Maximum operating conditions	Maximum inlet pressure:	0.34 MPa (3.4 bar, 50 psi) @ 25°C (77°F)
	Maximum forward/reverse differential pressure:	0.27 MPa (2.7 bar, 40 psi) @ 25°C (77°F)
	Maximum operating temperature:	40°C (104°F)
Compatibility	Cyclohexanone (CHN), methyl amyl ketone (MAK), n-butyl acetate (nBA), ethyl lactate (EL), propylene glycol methyl ether acetate (PGMEA), propylene glycol monomethyl ether (PGME), any blend of PGME/PGMEA	
Hold up volume	110 cc	
Typical flow rate	250 cc/min (20°C, 1 mPa*s) with 0.03 MPa pressure drop	

Preliminary specifications and features are subject to change.

DIMENSIONS



ORDERING INFORMATION

Part number	Description
EX1KCL0K1	Eximor SV1 Kalrez
EX00000K2	Eximor SV flushing shell Kalrez

FOR MORE INFORMATION

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